

FORM PTO-1449 US Dept. of Commerce  
Patent and Trademark Office

**INFORMATION DISCLOSURE STATEMENT**  
(use several sheets if necessary)

**ATTORNEY DOCKET NO.**  
ATMI-515

**SERIAL NO.**  
10/015,326

**APPLICANT**  
Chongying Xu, et al.

**FILING DATE**  
December 13, 2001

**GROUP**  
TBA

**U.S. PATENT DOCUMENTS**

EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
VM	AA	5,204,134	4/20/1993	Kirlin, et al.			
	AB	5,536,323	7/16/1996	Kirlin, et al.			
	AC	5,711,816	1/27/1998	Kirlin, et al.			
	AD	6,171,945	1/9/2002	Mandal, et al.			
	AE	4,745,169	5/17/1988	Sugiyama, et al.			
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	AO	4,156,689	5/29/1979	Ashby, et al.			
VM	AP	5,804,040	9/8/1998	Asai, et al.			

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		DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY	CLASS	SUBCLAS S	TRANSLATION YES NO	
							X (abstract only)	
VM	AQ	JP 50-111198	1/28/1974	Japan			X	

**OTHER DOCUMENTS (Including Author, Title, Journal-Date, Page Number, Etc.)**

VM	AR	Mantz, et al., "Thermolysis of Polyhedral Oligomeric Silsesquioxane (POSS) Macromers and POSS-Siloxane Copolymers", Chem. Mater., 1996, 8, pg. 1250-1259.
VM	AS	Ravi K. Laxman, Neil Hendrix Barry Arkles, Terry A. Tabler "Synthesizing Low-K CVD Materials for Fab Use" Semiconductor International, 11/1/2000

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**EXAMINER**  
V. Manoharan

**DATE CONSIDERED**  
2/24/03

**EXAMINER:** Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

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11	AT	Alfred Grill, et al., "Novel Low-k Dual-Phase Materials Prepared by PECVD, Mat. Res. Soc. Symp. Proc. Vol. 612, 2000 Materials Research Society
11	AU	Albert Wang, et al. "TMCTS for Gate Dielectric in Thin Film Transistors", Mat. Res. Soc. Meeting 1996
11	AV	A. Grill, et al., "Ultralow-k Dielectrics Prepared by Plasma-enhanced Chemical Vapor Deposition", Applied Physics Letters, Vol. 79, No. 6, Aug. 6, 2001.

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**Notice of References Cited**

Application/Control No.

10/015,326

Applicant(s)/Patent Under  
Reexamination  
XU ET AL.

Examiner

Virginia Manoharan

Art Unit

1764

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	B	US-4,127,598	11-1978	McEntee, Harry R.	558/442
	C	US-4,764,631	08-1988	Halm et al.	556/460
	D	US-5,312,947	05-1994	Tsukuno et al.	556/456
	E	US-6,368,359	04-2002	Perry et al.	8/142
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

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	N	0543685	05-1993	Europe	Shin-Etsu	
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	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
 Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.